



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Group Art Unit: 1732

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Lian-Cheng Zou, and Thomas R. McNeil**

Application No. 10/017,497

Filed: December 14, 2001

For: **ULTRAVIOLET LASER ABLATIVE
PATTERNING OF MICROSTRUCTURES
IN SEMICONDUCTORS**

Date: June 7, 2005

Examiner: Dr. Stefan Staicovici

AMENDMENT B

TO THE COMMISSIONER FOR PATENTS:

In response to the May 4, 2005 Office action, please amend the above-identified application as follows.

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks begin on page 9 of this paper.